

What is claimed is:

- 1           1.       A process for forming an article, comprising the steps of:  
2           providing a substrate, and  
3           forming on the substrate a film of  $(\text{BiEu})_3(\text{Fe}_{5-y}(\text{Ga}_x\text{Al}_{1-x})_y)\text{O}_{12}$ , where x is 0 to 1  
4           and y is 0.8 to 1.2,  
5           wherein the substrate is a single crystal material consisting essentially of a solid  
6           solution of two or more garnet materials, the substrate having a lattice parameter within  
7           0.004 Angstrom of the lattice parameter of the  $(\text{BiEu})_3(\text{Fe}_{5-y}(\text{Ga}_x\text{Al}_{1-x})_y)\text{O}_{12}$ .
- 1           2.       The process of claim 1, wherein x is 1, and the substrate lattice parameter  
2           is 12.53 to 12.555 Angstroms.
- 1           3.       The process of claim 1, wherein the substrate is of substantially uniform  
2           composition.
- 1           4.       The process of claim 1, wherein the substrate consists essentially of a solid  
2           solution of gadolinium scandium gallium garnet and gadolinium scandium aluminum  
3           garnet, or a solid solution of gadolinium scandium gallium garnet and terbium scandium  
4           gallium garnet.
- 1           5.       The process of claim 1, wherein y is selected such that the film exhibits a  
2           saturation magnetization, in absolute value, less than 100G at least at room temperature.
- 1           6.       The process of claim 5, wherein the film exhibits a substantially  
2           rectangular magnetization loop, a saturation magnetization, in absolute value, less than  
3           100G, a switching field, in absolute value, higher than the saturation magnetization, in a  
4           magnetic field applied parallel to the normal to the major surface of the film, over an  
5           operating temperature range of  $-40^\circ\text{C}$  to  $+85^\circ\text{C}$ .

1           7.     The process of claim 6, wherein the film exhibits a switching field, in  
2 absolute value, of at least 200 Oe over the operating temperature range, and a switching  
3 field, in absolute value, of at least 500 Oe at least at room temperature.

1           8.     The process of claim 7, wherein the film exhibits a switching field, in  
2 absolute value, of 500 Oe or higher over the operating temperature range.

1           9.     The process of claim 1, further comprising the steps of:  
2 processing the film to form chips, and  
3 incorporating at least one chip into a device.

1           10.    The process of claim 1, wherein the lattice parameter is within 0.002  
2 Angstrom of the lattice parameter of the  $(\text{BiEu})_3(\text{Fe}_{5-y}(\text{Ga}_x\text{Al}_{1-x})_y)\text{O}_{12}$ .

1           11.    A process for forming an article, comprising the steps of:  
2 providing a substrate, and  
3 forming on the substrate a film of  $(\text{BiEu})_3(\text{Fe}_{5-y}(\text{Ga}_x\text{Al}_{1-x})_y)\text{O}_{12}$ , where x is 0 to 1  
4 and y is 0.8 to 1.2,  
5 wherein the substrate is a single crystal material consisting essentially of a solid  
6 solution of gadolinium scandium gallium garnet and gadolinium scandium aluminum  
7 garnet, or a solid solution of gadolinium scandium gallium garnet and terbium scandium  
8 gallium garnet.

1           12.    The process of claim 11, where x is 1.

1           13.    The process of claim 12, wherein the substrate lattice parameter is 12.53 to  
2 12.555 Angstroms.

1           14.    The process of claim 13, wherein the substrate is of substantially uniform  
2 composition.

1           15.    The process of claim 11, wherein y is selected such that the film exhibits a  
2 saturation magnetization, in absolute value, less than 100G at least at room temperature.

1           16.    The process of claim 15, wherein the film exhibits a substantially  
2 rectangular magnetization loop, a saturation magnetization, in absolute value, less than  
3 100G, a switching field, in absolute value, higher than the saturation magnetization, in a  
4 magnetic field applied parallel to the normal to the major surface of the film, over an  
5 operating temperature range of  $-40^{\circ}\text{C}$  to  $+85^{\circ}\text{C}$ .

1           17.    The process of claim 13, wherein the film exhibits a switching field, in  
2 absolute value, of at least 200 Oe over the operating temperature range, and a switching  
3 field, in absolute value, of at least 500 Oe at least at room temperature.

1           18.    The process of claim 17, wherein the film exhibits a switching field, in  
2 absolute value, of 500 Oe or higher over the operating temperature range.

1           19.    The process of claim 11, further comprising the steps of:  
2 processing the film to form chips, and  
3 incorporating at least one chip into a device.

1           20.    An article comprising the film according to claim 1.

1           21.    An article comprising the film according to claim 4.